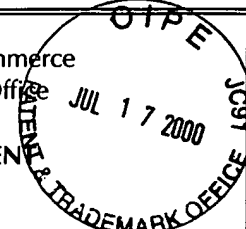


<b>Form PTO-1449</b> U.S. Department of Commerce (Rev. 8-83) Patent and Trademark Office		Atty. Docket No.: 0756-1630		Serial No. 08/799,506	
<b>INFORMATION DISCLOSURE STATEMENT</b> (Use several sheets if necessary)		Applicant: Shunpei YAMAZAKI, et al.			
		Filing Date: February 12, 1997		Group: 2822	



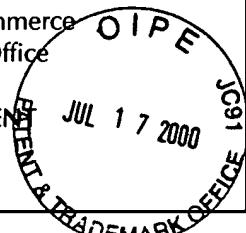
U.S. PATENT DOCUMENTS							
Examiner Initial	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if approp.)	
MW	5,581,092	12/03/96	Takemura	X	X		
MW	5,595,638	01/21/97	KONUMA ET AL.				
MW	5,608,232	03/04/97	YAMAZAKI ET AL.				
MW	5,608,251	03/04/97	KONUMA ET AL.				
MW	5,620,095	04/15/97	KONUMA ET AL.				
MW	5,639,698	06/17/97	YAMAZAKI ET AL.				
MW	4,151,058	04/24/79	KAPLAN				
MW	4,226,898	10/07/80	OVSHINSKY				
MW	4,313,783	02/02/82	DAVIES ET AL.				
MW	4,322,253	03/30/82	PANKOVE				

FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation		
MW	01-128446	JAPAN	X	X	Yes	No	
MW	02-257619	JAPAN			ABST.		
MW	04-206532	JAPAN			ABST.		
MW	05-182923	JAPAN			ABST.		
MW	57-194518	JAPAN			ABST.		
MW	64-076737	JAPAN			ABST.		
MW	0211634	EP			FULL		

OTHER DOCUMENTS (Including Author, Title, Relevant Pages, Date, Place of Publication)	
MW	Kawashi, et al., "LARGE-AREA DOPING PROCESS FOR FABRICATION OF poly-SI THIN FILM TRANSISTORS USING BUCKET ION SOURCE AND XeCl EXCIMER LASER ANNEALING," Japanese Journal of Applied Physics, No. 12, December, pp. L2370-L2372.
MW	Sameshima, et al., "XeCl EXCIMER LASER ANNEALING USED TO FABRICATE POLY-Si TFT's," Japanese Journal of Applied Physics, Vol. 28, No. 10, October 1989, pp. 1789-1793.
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MW	Sera, et al., "HIGH-PERFORMANCE TFT'S FABRICATED BY XeCl EXCIMER LASER ANNEALING OF HYDROGENATED AMORPHOUS-SILICON FILM," IEEE Transactions on Electron Devices, Col. 36, No. 12, December 1989, pp. 2868-2872.
Examiner <u>MWileczewski</u>	
Date Considered <u>9/2000</u>	

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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Filing Date: February 12, 1997		Group: 2822			



U.S. PATENT DOCUMENTS							
Examiner Initial	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if approp.)	
MW	4,370,175	01/25/83	LEVATTER				
MW	4,388,145	06/14/83	HAWKINS ET AL.				
MW	4,402,762	09/06/83	JOHN ET AL.				
MW	4,405,435	09/20/83	TATEISHI ET AL.				
MW	4,498,416	02/12/85	BOUCHAIB				
MW	4,503,807	03/12/85	NAKAYAMA ET AL.				
MW	4,523,370	06/18/85	SULLIVAN ET AL.				
MW	4,552,595	11/12/85	HOGA				
MW	4,557,036	12/10/85	KYURAGI ET AL.				
MW	4,567,061	01/28/86	HAYASHI ET AL.				

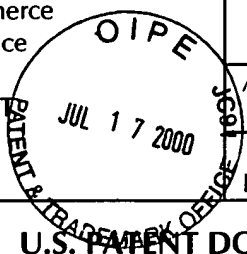
FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation Yes No		
MW	60-042817	03/07/85	JAPAN				X
MW	63-160336	07/04/88	JAPAN			ABST.	
MW	01-179410	07/17/89	JAPAN			ABST.	
MW	03-024717	02/01/91	JAPAN			ABST.	
MW	62-104117	05/14/87	JAPAN			FULL	
MW	02-239615	09/21/90	JAPAN			FULL	
MW	02-081424	03/22/90	JAPAN			ABST.	

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MW	Kuwano, et al., "PHOTOVOLTAIC BEHAVIOR OF AMORPHOUS Si:H AND Si:F:H SOLAR CELLS," Conference Record, 15 <sup>th</sup> IEEE Photovoltaic Specialists Conf., Kissimmee, Florida, USA, May 12-15, 1981, Published August 1981.

Examiner <i>MWitczewski</i>	Date Considered <i>9/2000</i>
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Examiner Initial		Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if approp.)
MW		4,576,851	03/18/86	IWAMATSU			
MW		4,582,720	04/15/86	YAMAZAKI			
MW		4,589,951	05/20/86	KAWAMURA			
MW		4,590,091	05/20/86	ROGERS ET AL.			
MW		4,592,306	06/03/86	GALLEGO			
MW		4,592,799	06/03/86	HAYAFUJI			
MW		4,595,601	06/17/86	HORIOKA ET AL.			
MW		4,609,407	09/02/86	MASAO ET AL.			
MW		4,640,223	02/03/87	DOZIER			
MW		4,694,143	09/15/87	NISHIMURA ET AL.			

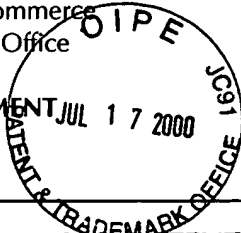
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation Yes No

OTHER DOCUMENTS (Including Author, Title, Relevant Pages, Date, Place of Publication)		

Examiner <i>MWileczewski</i>	Date Considered <i>9/00</i>
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Examiner Initial		Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if approp.)
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MW		4,699,863	10/13/87	SAWATARI ET AL.			
MW		4,719,123	01/12/88	HAKU ET AL.			
MW		4,843,022	06/27/89	YAMAZAKI			
MW		4,951,601	08/28/90	MAYDAN ET AL.			
MW		4,986,213	01/22/91	YAMAZAKI ET AL.			
MW		5,091,334	02/25/92	YAMAZAKI			
MW		5,141,058	08/25/92	HEPPNER			
MW		5,171,710	12/15/92	YAMAZAKI			
MW		5,296,405	03/22/94	YAMAZAKI ET AL.			


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		Document Number	Date	Country	Class	Subclass	Translation Yes No

OTHER DOCUMENTS (Including Author, Title, Relevant Pages, Date, Place of Publication)							

Examiner <i>MWilczewski</i>	Date Considered <i>9/2000</i>
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Examiner Initial		Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if approp.)
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MW		4,151,007	04/24/74	LEVINSTEIN ET AL.			
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MW		4,398,343	08/16/83	TAMAZAKI			
MW		4,482,395	11/13/84	HIRAMOTO			
MW		5,424,244	06/13/95	ZHANG ET AL.			
MW		5,840,600	11/24/98	YAMAZAKI ET AL.			
MW		5,879,969	03/09/99	YAMAZAKI ET AL.			
MW		5,294,811	03/15/94	AOYAMA ET AL.			

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		Document Number	Date	Country	Class	Subclass	Translation Yes No

OTHER DOCUMENTS (Including Author, Title, Relevant Pages, Date, Place of Publication)		

Examiner <i>MW/iczewski</i>	Date Considered <i>9/2000</i>
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